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### AMENDMENTS TO THE CLAIMS

Claim 1-6 (canceled)

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- 5 Claim 7 (original): A light emitting diode having a transparent substrate, the light emitting diode comprising:
  - a transparent substrate:
  - an amorphous interface layer formed on the transparent substrate;
  - a top surface of the amorphous interface layer comprising a first surface region and a second surface region;
  - a p<sup>+</sup>-type contact layer formed on the first surface region;
  - a p-type cladding layer formed on the p+-type contact layer;
  - a multiple quantum well (MQW) light-emitting layer formed on the p-type cladding layer;
  - an n-type cladding layer formed on the MQW light-emitting layer;
    - an n-type stop layer formed on the n-type cladding layer;
    - a transparent conductive layer formed on the n-type stop layer;
    - a first electrode formed on the transparent conductive layer; and
    - a second electrode formed on the second surface region.

Claim 8 (currently amended): A light emitting diode having a transparent substrate, the light emitting diode comprising:

- a transparent substrate comprising sapphire;
- an amorphous interface layer formed on the transparent substrate, a top surface

  of the amorphous interface layer comprising a first surface region and a
  second surface region;
  - a contact layer of p+-type GaAs formed on the first surface region;
  - a p-type cladding layer of p-type AlGaInP formed on the contact layer[[.]];
  - a light-emitting layer of AlGaInP formed on the p-type cladding layer;

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an n-type cladding layer of n-type AlGaInP formed on the light-emitting layer; a stop layer of n-type AlGaAs formed on the n-type cladding layer; an indium tin oxide (ITO) transparent conductive layer formed on the stop layer[[.]];

a first electrode formed on the ITO transparent conductive layer[[.]]; and a second electrode formed on the second surface region.

Claim 9 (original): A light emitting diode having a transparent substrate, the light emitting diode comprising:

an ohmic contact electrode;
a p-type transparent substrate formed on the ohmic contact electrode;

a first p<sup>+</sup>-type contact layer formed on the transparent substrate;

an amorphous interface layer formed on the first p<sup>+</sup>-type contact layer;

a second p+-type contact layer formed on the amorphous interface layer;

a p-type cladding layer formed on the second p+type contact layer;

a light-emitting layer formed on the p-type cladding layer;

an n-type cladding layer formed on the light-emitting layer;

an n-type stop layer formed on the n-type cladding layer;

a transparent conductive layer formed on the n-type stop layer; and

a first electrode formed on the transparent conductive layer.

Claim 10 (currently amended): A light emitting diode having a transparent substrate, the light emitting diode comprising:

an ohmic contact electrode;

25 a p-type GaP transparent substrate formed on the ohmic contact electrode;

a first p<sup>+</sup>-type contact layer of p<sup>+</sup>-type GaAs formed on the p-type GaP transparent substrate;

an indium tin oxide amorphous interface layer formed on the first p<sup>+</sup>-type contact layer;

- a second p<sup>+</sup>-type contact layer of p<sup>+</sup>-type GaAs formed on the indium tin oxide amorphous interface layer;
- a p-type cladding layer of a p-type AlGaInP formed on the second p<sup>+</sup>-type contact layer;
- a multiple quantum well light-emitting layer of AlGaInP formed on the p-type cladding layer;

an n-type cladding layer of n-type AlGaInP formed on the light-emitting layer; a stop layer of n-type AlGaAs formed on the n-type cladding layer; an indium tin oxide (ITO) transparent conductive layer formed on the stop layer;

a first electrode formed on the ITO transparent conductive layer.

Claim 11 (original): A light emitting diode having a transparent substrate, the light emitting diode comprising:

a first electrode;

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an n-type transparent substrate formed on the first electrode;

an amorphous interface layer formed on the n-type transparent substrate;

an n-type contact layer formed on the amorphous interface layer;

an n-type cladding layer formed on the n-type contact layer;

a light-emitting layer formed on the n-type cladding layer;

a p-type cladding layer formed on the light-emitting layer;

a p-type buffer layer formed on the p-type cladding layer;

a p\*-type contact layer formed on the p-type buffer layer:

a transparent conductive layer formed on the p+-type contact layer; and

a second electrode formed on the transparent conductive layer.

Claim 12 (currently amended): A light emitting diode having a transparent substrate, the light emitting diode comprising:

a first electrode;

a transparent substrate of n-type GaP formed on the first electrode;

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- an indium tin oxide (ITO) amorphous interface layer formed on the transparent substrate of n-type GaP;
- a contact layer of n-type GaP formed on the ITO amorphous interface layer;
- a cladding layer of n-type AlGaInP formed on the contact layer of n-type GaP;
- a multiple quantum well (MQW) light-emitting layer of AlGaInP formed on the cladding layer of n-type AlGaInP;
- a cladding layer of p-type AlGaInP formed on the MQW light-emitting layer of AlGaInP;
- a buffer layer of p-type AlGaAs formed on the cladding layer of p-type AlGaInP;
- a contact layer of p+type GaAs formed on the buffer layer of p-type AlGaAs;
- an <u>indium tin oxide (ITO)</u> transparent conductive layer formed on the contact layer of p<sup>+</sup>-type GaAs; and
- a second electrode formed on the ITO transparent conductive layer.

Claim 13 (original): A light emitting diode having a transparent substrate, the light emitting diode comprising:

a transparent substrate;

an amorphous interface layer formed on the transparent substrate, a top surface of the amorphous interface layer comprising a first surface region and a second surface region;

an n+type reverse-tunneling contact layer formed on the first surface region;

- a p-type cladding layer of formed on the n+type reverse-tunneling contact layer;
- a light-emitting layer formed on the p-type cladding layer;
- an n-type cladding layer formed on the light-emitting layer;
  - a first contact electrode formed on the n-type cladding layer; and
  - a second electrode formed on the second surface region.

Claim 14 (original): A light emitting diode having a transparent substrate, the light

#### emitting diode comprising:

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- a transparent substrate comprising glass;
- an indium tin oxide (ITO) amorphous interface layer formed on the transparent substrate, a top surface of the ITO amorphous interface layer comprising a first surface region and a second surface region;
- a reverse-tunneling contact layer of n<sup>+</sup>-type InGaN formed on the first surface region;
- a cladding layer of a p-type GaN formed on the reverse-tunneling contact layer of n<sup>+</sup>-type InGaN;
- a multiple quantum well (MQW) light-emitting layer of InGaN formed on the cladding layer of a p-type GaN;
- a cladding layer of n-type GaN formed on the MQW light-emitting layer of InGaN;
- a first contact electrode formed on the cladding layer of n-type GaN;
- 15 a second electrode formed on the second surface region.

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